



## Polycarbonate Chemical Resistance

**E = excellent resistance: no etching**

**B=Good res. little etching after 30 days exposure to reagent.**

**S= Fair resistance, etching after 7 days exposure to reagent**

**N= not recommended**

Reagent	PC	
	20°C	50°C
Actaldehyde	S	N
Acetone	N	N
Acetic acid	E	B
Aluminum hydroxide	S	N
Ammonium chlodide	E	E
Ammonium hydroxide 5%	S	N
Ammonium hydroxide 28%	N	N
Amyl chloride	N	N
Aniline	S	N
Banzaldehyde	S	N
Benzene	N	N
Boric acid	E	E
Bromine	S	N
Bromoform	N	N
Butadiene	N	N
Butyl acetate	N	N
Butyl Alcohol	B	S
Butyric acid	S	N
Calcium hydroxide	N	N
Calcium hypochloride	S	N
Carbon disulphide	N	N
Carbon tetrachloride	N	N
Cellosolve	S	N
Chlorine in air	E	B
Chlorine (moist)	B	S
Chloroform	N	N
Citric add.	E	E



Cresol	N	N
Cyclohexane	E	B
p-dichlorobenzene	N	N
Diethylene glycol	B	S
Diethylene formamide	N	N
Dioxane	B	S
Ethyl acetate	N	N
Ethyl alcohol	E	B
Ethyl chloride	N	N
Ethylene chloride	N	N
Ethylene oxide	S	N
Ethyl ether	N	N
Formaldehyde	E	B
Formic acid	E	S
Gasoline	S	S
Hexane	N	N
Hydrochloric acid 35%	N	N
Hydrofluoric acid	N	N
Hydrogen peroxide	E	E
Kerosene	B	S
Lactic acid	E	B
Methyl alcohol	B	S
Methyl ethyl ketone	N	N
Methyl isobutyl ketone	N	N
Methylene chloride	N	N
Mineral oil	E	B
Nitric acid 1-10%	E	B
Nitric acid 50%	B	S
Nitric acid 65%	S	N
Nitrobenzene	N	N
Perchloric acid	N	N
Petroleum ether	S	N
Phenol	E	N
Phosphoric acid 85%	E	B
Potassium bichromate	E	B
Potassium hydroxide conc.	N	N
Potassium permanganate	E	B
Propane	S	N



Propylene glycol	S	N
Silver nitrate	B	S
Sodium hydroxide conc.	S	S
Sodium hypochloride	N	N
Sulfuric acid 20%	B	S
Sulfuric acid 98%	E	B
Tetrahydrofuran	N	N
Thionil chloride	N	N
Toluene	N	N
Trichloroacetic acid	S	N
sim-trichloroethane	N	N
Trichloroethylene	N	N
Turpentine	S	N
Urea	N	N
Xylene	N	N